

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	19	("2250556" "2931760" "3915809" "4350564" "5294326" "5425822"). PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/05 16:09
S2	1322	(substrate material) and ((metal adj (film layer)) cr chromium titanium ti tungsten w wolfram palladium pd molybdenum mo) and (((second adj (metal adj (film layer))) al aluminum copper cu gold au silver ag) with (pattern pattern\$3)) and ((positive adj electrode) (anode adj (plate mesh)) anode) and (((acid acid\$3) adj (electrolyte solution)) ((hydrochloric sulfuric carboxylic hydrofluoric phosphoric orthophosphoric) adj acid) HCl H2SO4 H2CO3 CH3COOH C2O2H4 HF H3PO4) and ((reduction reduc\$3 remov\$3) with ((passivation passivat\$3 oxidiz\$3 oxidation oxide) near3 (layer film cr chromium titanium ti tungsten w wolfram palladium pd molybdenum mo))) and (etch etch\$3 polish polish\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/05 13:04
S3	697	(substrate material) and ((etch etch\$3 polish polish\$3) with ((metal adj (film layer)) cr chromium titanium ti tungsten w wolfram palladium pd molybdenum mo)) and (((second adj (metal adj (film layer))) al aluminum copper cu gold au silver ag) with (pattern pattern\$3)) and ((positive adj electrode) (anode adj (plate mesh)) anode) and (((acid acid\$3) adj (electrolyte solution)) ((hydrochloric sulfuric carboxylic hydrofluoric phosphoric orthophosphoric) adj acid) HCl H2SO4 H2CO3 CH3COOH C2O2H4 HF H3PO4) and ((reduction reduc\$3 remov\$3) with ((passivation passivat\$3 oxidiz\$3 oxidation oxide) near3 (layer film cr chromium titanium ti tungsten w wolfram palladium pd molybdenum mo)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/05 13:25

EAST Search History

S4	76	(substrate material) and ((etch etch\$3 polish polish\$3) with ((metal adj (film layer)) cr chromium titanium ti tungsten w wolfram palladium pd molybdenum mo)) and (((second adj (metal adj (film layer))) al aluminum copper cu gold au silver ag) with (pattern pattern\$3)) and (((acid acid\$3) adj (electrolyte solution)) ((hydrochloric sulfuric carboxylic hydrofluoric phosphoric orthophosphoric) adj acid) HCl H2SO4 H2CO3 CH3COOH C2O2H4 HF H3PO4) and (((positive adj electrode) (anode adj (plate mesh)) anode) same ((reduction reduc\$3 remov\$3) with ((passivation passivat\$3 oxidiz\$3 oxidation oxide) near3 (layer film cr chromium titanium ti tungsten w wolfram palladium pd molybdenum mo))))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/05 13:27
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